

ABSTRACT OF THE DISCLOSURE

*(S2A2)* A polishing apparatus comprises a top ring for holding a workpiece to be polished, and a polishing table movable relatively to the top ring. The polishing table has a 5 polishing surface for polishing the workpiece held by the top ring. The polishing apparatus further comprises a polishing liquid supply device for supplying a polishing liquid to the polishing surface. At least one of the top ring and the polishing table reciprocates linearly in a first direction. 10 The workpiece can be polished uniformly by the polishing surface because at least one of the top ring and the polishing table reciprocates linearly in the first direction.